

Figure 1. Atomic models for (a) (110) and (b) (010) planes projected along [001] direction

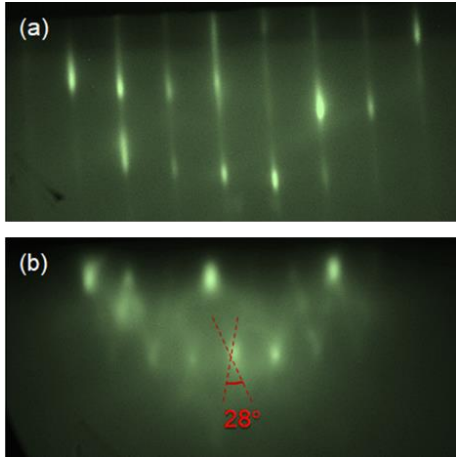


Figure 2. RHEED pattern of (a) (110) substrate and (b) (010) substrate after Ga polishing

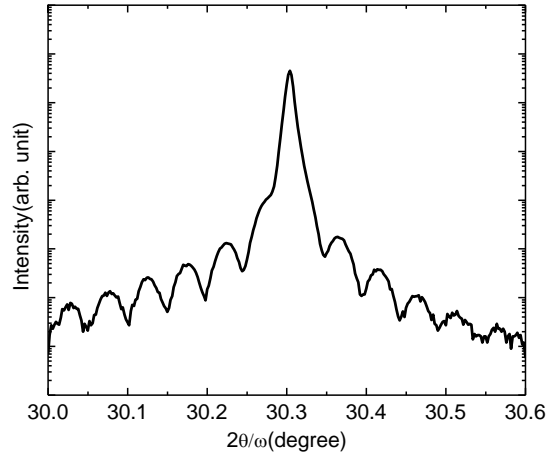


Figure 3. HRXRD patterns of  $\beta$ -Ga<sub>2</sub>O<sub>3</sub> films grown on (110) substrate

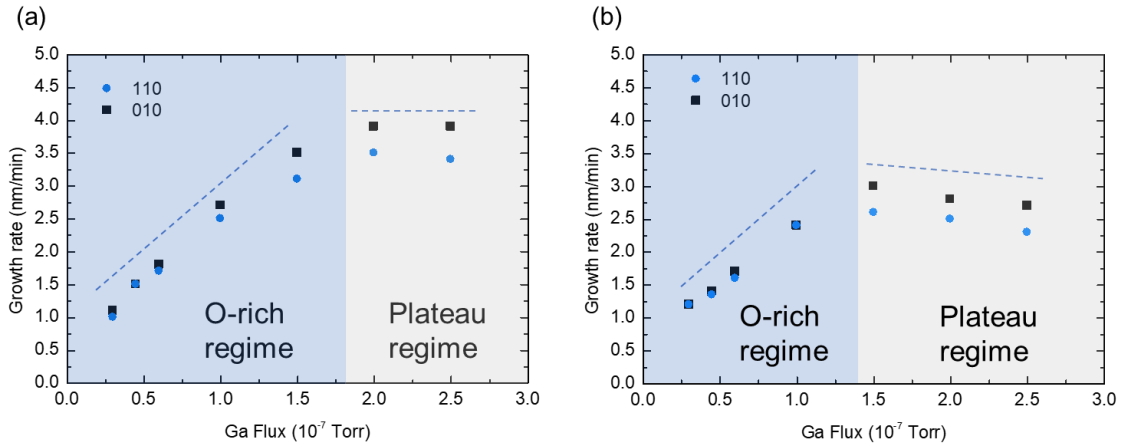


Figure 4.  $\beta$ -Ga<sub>2</sub>O<sub>3</sub> films grown on (110) and (010) substrates at (a) 600 °C and (b) 700 °C

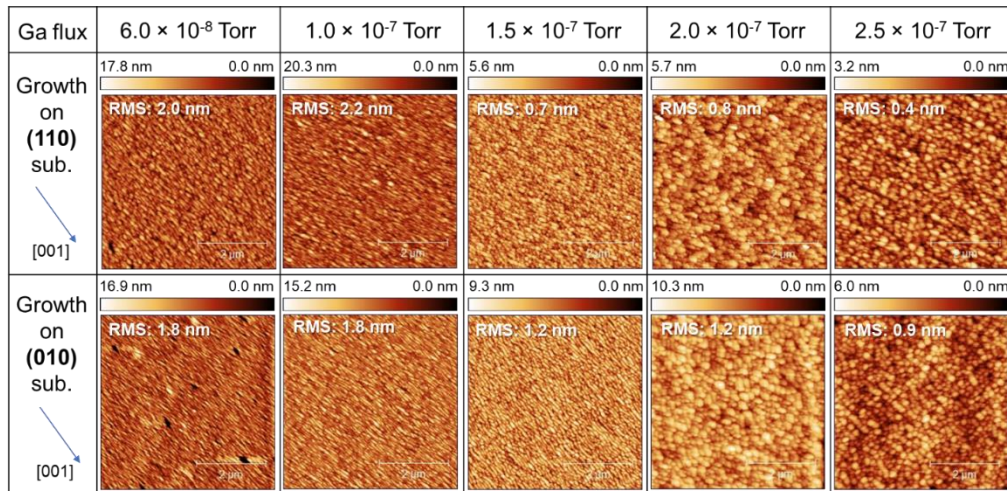


Figure 5. AFM images of  $\beta$ -Ga<sub>2</sub>O<sub>3</sub> films grown on (110) and (010) substrates at 700 °C